

Notice of References Cited	Application/Control No. 10/604,651	Applicant(s)/Patent Under Reexamination PENG ET AL.	
	Examiner Alexander G. Ghyka	Art Unit 2812	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,610,142	08-2003	Takayama et al.	117/8
*	B	US-5,563,093	10-1996	Koda et al.	438/231
	C	US-			
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	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	JEN et al, Effects of N2O Plasma Treatment, Japanese Journal of Applied Physics, Part 2, Letter 1994
	V	LUAN et al, Effects of NH3 Plasma, J. of Applied Physics, 68 (7), October 1990
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

Alex Ghyka 2/15/07